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54 Substrate for planographic plate.

(57) Disclosed is a substrate for planographic (lithographic) plate, which comprises metal foils with thicknesses of 5 to 100 µ laminated on both surfaces of a sheet with a thickness of 30 to 400 µ, said sheet being obtained by sheet making of a modified polyolefin composite material comprising 100 parts by weight of a modified polyolefin resin graft-modified partially or wholly with an organic silane compound and 5 to 150 parts by weight of mica.



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